

Status of Sensors:

Sensors and bump-bonding

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- Status of sensor and bump-bonding
- Some observed issues
- Summary

Status



Sensors:

- 2 batches received from Sintef

	Batch-1	Batch-2	Sum
Nr. wafers* received	20	25	45
Nr. cut wafers	2	2	4
Nr. processed** wafers	14	0	14
Nr. remaining wafers	4	23	27

^{* 1} wafer \rightarrow 2 sensors

Bump-bonding:

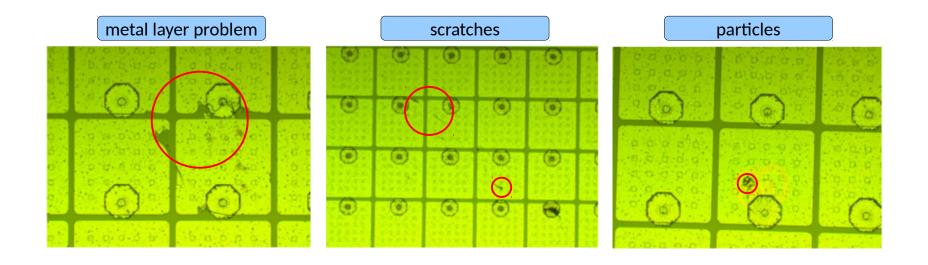
- new bonding machine
- effort made to make bonding properly

^{**} processed wafer → UBM, bump deposition (Dectris) & cut

Some observed issues



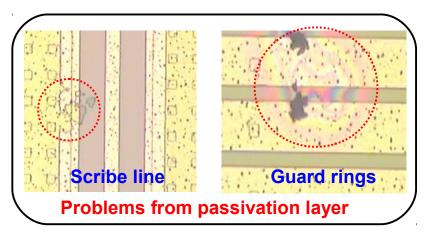
- Issues observed in UBM & bump deposition processes (by Dectris):
 - metal adhesion
 scratches
 particles on/inside passivation

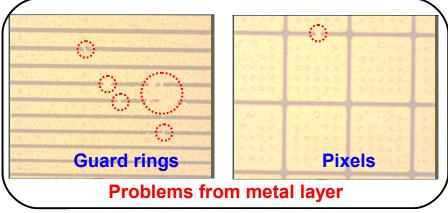


Similar observations through visual inspection at UHH!

Reminder: Visual inspection AGIPD

- Visual inspection for pixels and guard-ring structure of ~ 10 wafers
 - problems observed for passivation and metalisation

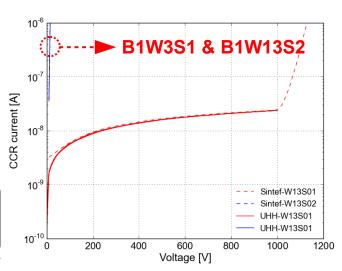




- Judged as bad sensor by Sintef from I-V measurement; actual problems observed through visual inspection at HH
- Information stored (12k images/sensor)
 - → "trace back" in case problem

Metal adhesion:

- in GRs: early breakdown (2 sensors)
- in pixels: loss spatial resolution (2/65536 pixels)



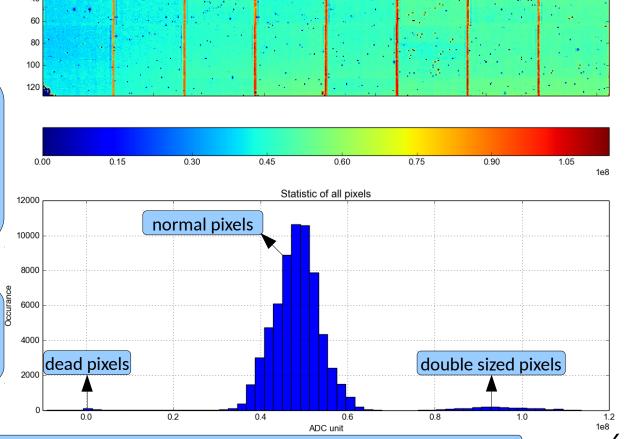
Bad pixels



Bad pixels (= sensor pixels + ASIC pixels + unbonded bumps)

20

- flat-field image
- dark-field corrected
- ADC gain corrected
- ~ 0.6% bad pixels (estimate):
- \rightarrow <0.1% from ASICs
- \rightarrow ~0.2% from unbonded bumps:
 - * 0.08% due to bonding
 - * 0.12% due to size of indium ball
- \rightarrow ~0.3% from sensor:
 - * < 0.2% hot pixel
 - * others
- "Trace back" sensor inspection:
- → metal adhesion: 1
- → scratch: 0
- → particles: ~ 604



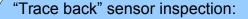
X-ray image of module with "contaminated" sensor

"Contaminated" sensor (more sticky particles)! → check other modules!

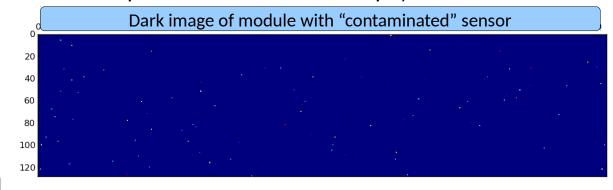
Bad pixels

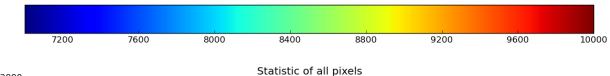


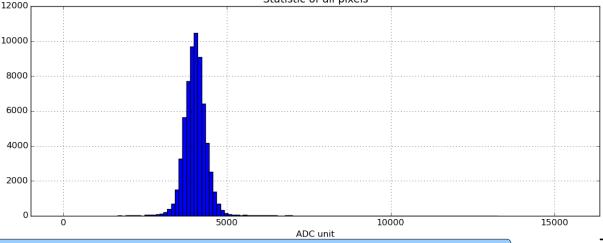
- Bad pixels (= sensor pixels + ASIC pixels + unbonded bumps)
 - flat-field image
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- → metal adhesion: 1
- → scratch: 0
- → particles: ~ 604







Summary



- Issues observed for sensors (by Dectris & previously@UHH)
- Measurement for sensor after bump-bonding:
 - bad pixel: ~ 0.6% for a "contaminated" sensor
 - ~ 0.4% non-working pixels
 - ~ 0.2% hot (noisy) pixels
- Following work and plan:
 - check results for "non-contaminated" sensors
 - quick inspection on sensor before bump-bonding
 - optimize bump-bonding process and improve bonding yield
 - discuss the issue with sensor vendor

Be aware: statistic is 1!



Spin coating (lift-off-resist) and printing of photoresist

Sensor wafer (100 mm) CMOS wafer (200 mm) Aluminium Passi vation (a) Resist spin-on and exposure Mask _ Photo Resist (b) LOR" Resist development (c) (k) Sputtered UBM (d) Wet lift-off (e) Evaporated Indium (f) Wet lift-off Reflow (h)

Photoresist stripping and wet etching

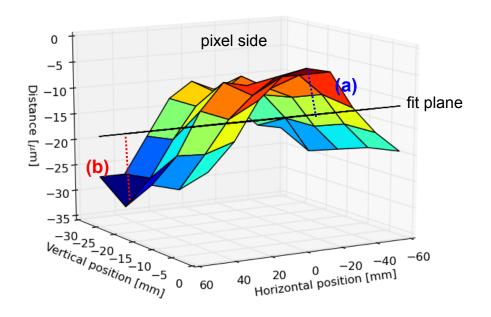
Sensor flatness

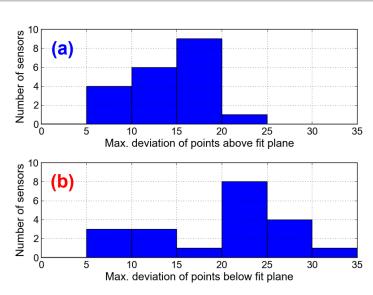


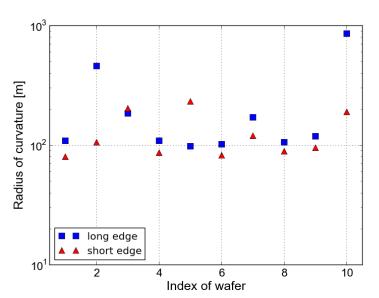
Flatness measurement

- fit to a plane for individual sensor:
- radius of curvature: ~ 100 m
- max. force on a bond pad (0.01 0.1 mN)
 (bonding force: , de-bonding:)

Measurement & Fit for Sensor-1

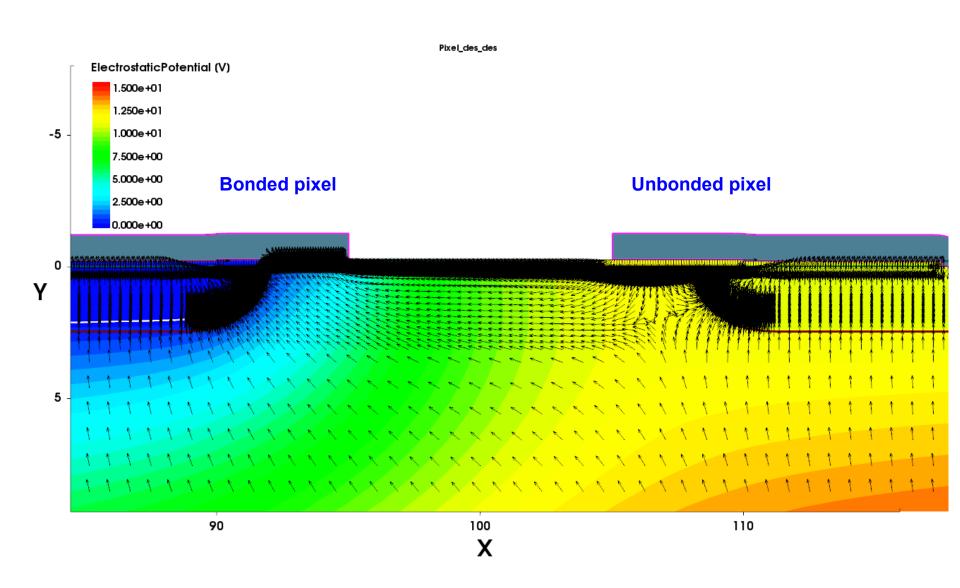






Electric field





Weighting potential



2D simulation

Bonded pixel Unbonded pixel Bonded pixel

